

Contents

PART I INTRODUCTION

1. Vapor-Deposited Materials, JOHN M. BLOCHER, JR.	3
<i>Fundamentals</i>	5
<i>Techniques</i>	16
<i>Applications</i>	17

PART II FUNDAMENTALS

2. Thermodynamics, ALFRED C. LOONAN	25
<i>Physical Transport Processes</i>	28
<i>Chemical Transport Processes</i>	31
<i>Discussion</i>	55
3. Evaporation Processes, JOSEPH F. DETTORRE, THOMAS G. KNORR, AND ELTON H. HALL	62
<i>Thermal Evaporation</i>	62
<i>Sputtering</i>	78
<i>Chemical Evaporation</i>	88
4. Transport Processes, JOSEPH H. OXLEY	102
<i>Diffusional Relationships</i>	107
<i>Mass-Transfer Coefficient</i>	108
<i>Effective Area</i>	112
<i>Diffusion Potential</i>	116
5. Condensation Processes, J. P. HIRTH	126
<i>Heterogeneous Nucleation</i>	127
<i>Crystal Growth</i>	137
6. Structure of Deposits, RONALD D. GRETZ	149
<i>Bimodal Structures</i>	150
<i>Epitaxy and Oriented Overgrowth</i>	157
<i>Morphology</i>	173

7. Stresses in Deposits, CARROLL F. POWELL	191
<i>Physical Vapor Deposition</i>	194
<i>Chemical Vapor Deposition</i>	198

PART III TECHNIQUES

8. Physical Vapor Deposition, CARROLL F. POWELL	221
<i>Evaporation Temperatures and Rates</i>	222
<i>Apparatus</i>	223
<i>Surface Preparation</i>	235
<i>Deposition Efficiency and Distribution</i>	237
<i>Deposition of Alloys and Mixtures</i>	242
9. Chemical Vapor Deposition, CARROLL F. POWELL	249
<i>Process Considerations</i>	250
<i>Coating Characteristics</i>	259
<i>Apparatus Designs</i>	263
10. Chemically Deposited Metals, CARROLL F. POWELL	277
<i>Aluminum and Aluminides</i>	277
<i>Antimony, Arsenic, and Bismuth</i>	283
<i>Beryllium</i>	285
<i>Chromium</i>	290
<i>Cobalt</i>	294
<i>Copper</i>	296
<i>Germanium</i>	297
<i>Gold</i>	298
<i>Hafnium</i>	299
<i>Iron</i>	300
<i>Lead</i>	301
<i>Molybdenum</i>	302
<i>Nickel</i>	305
<i>Niobium and Tantalum</i>	307
<i>Platinum-Group Metals</i>	310
<i>Rhenium</i>	314
<i>Thorium</i>	316
<i>Tin and Stannides</i>	316
<i>Titanium</i>	319
<i>Tungsten</i>	322
<i>Uranium</i>	326
<i>Vanadium</i>	327
<i>Zirconium</i>	328
11. Chemically Deposited Nonmetals, CARROLL F. POWELL	343
<i>Boron and Borides</i>	343

<i>Carbon and Carbides</i>	352
<i>Nitrides</i>	378
<i>Oxides</i>	384
<i>Silicon and Silicides</i>	403

PART IV APPLICATIONS

12. Pigments and Reinforcing Agents, EUGENE J. MEZEY	423
<i>The Oxides</i>	424
<i>Carbon Blacks</i>	439
13. High-Purity Metals, JOSEPH H. OXLEY	452
<i>Batch Processes</i>	453
<i>Flow Processes</i>	463
14. Nuclear Fuels, JOSEPH H. OXLEY	484
<i>Materials Production</i>	488
<i>Irradiation Behavior</i>	498
<i>Coating Costs</i>	504
15. Protective Coatings, C. A. KRIER	512
<i>Coating-Substrate System</i>	513
<i>Wear-Resistant Coatings</i>	522
<i>Corrosion-Resistant Coatings</i>	526
<i>Oxidation-Resistant Coatings</i>	530
16. Optical Coatings, OSMAR A. ULLRICH	549
<i>Reflective Coatings</i>	556
<i>Antireflective Coatings</i>	559
<i>Absorptive Coatings</i>	561
<i>Spectrally Selective Interference Coatings</i>	563
<i>Electro-optical Coatings</i>	569
<i>Phase-Altering Coatings</i>	570
<i>Coatings for Analytical Purposes</i>	571
<i>Monitoring of Coating Process</i>	572
17. Decorative Coatings, FREDERIC J. HORN AND HOWARD B. HEBBLE, JR.	579
<i>Basic Batch Process</i>	582
<i>Continuous Processes</i>	584
<i>Substrate Considerations</i>	585
<i>Design Considerations</i>	587
18. Electronic Materials, WALTER R. RUNYAN	593
<i>Silicon Manufacture</i>	594
<i>Germanium Manufacture</i>	602
<i>Coating Materials</i>	602
<i>Deposition of Contacts</i>	606

CONTENTS

19. Epitaxial Materials, B. SCHWARTZ	612
<i>Silicon</i>	613
<i>Germanium</i>	624
<i>Gallium Arsenide</i>	630
<i>Heterojunctions</i>	634
<i>Measurements</i>	635
20. Structural Shapes, JOHN M. BLOCHER, JR.	650
<i>Vapor Forming</i>	651
<i>Vapor Joining</i>	681
<i>Vapor Consolidation</i>	684
Author Index	693
Materials Index	715